

WHAT IS CLAIMED IS:

1. A method of making a polishing pad, comprising:

forming an aperture through a polishing layer stack from a polishing surface to a bottom surface of the polishing layer stack to expose a first adhesive layer that is positioned on and contacts the bottom surface of the polishing layer stack and spans the aperture and the polishing pad, the polishing layer stack including a polishing layer having the polishing surface, wherein the first adhesive layer secures the bottom surface of the polishing layer stack to a fluid-impermeable layer that spans the aperture and the polishing pad;

positioning a pre-formed light-transmitting body in the aperture in the polishing layer stack such that a lower surface of the light-transmitting body contacts and adheres to the first adhesive layer;

dispensing an adhesive sealant into a gap that separates the light-transmitting body from side-walls of the aperture to laterally fill the gap; and

curing the adhesive sealant,

wherein forming the aperture comprises peeling a disposable cover away from the first adhesive layer while leaving a majority of the first adhesive layer in the aperture on the fluid-impermeable membrane, wherein the disposable cover is a different material than the polishing layer.